

10/522036

**NATIONAL PHASE
UTILITY APPLICATION**

Attorney Docket No.: SHIGA7.004APC
 First Named Inventor: Kenji MARUYAMA
 Int'l Application No.: PCT/JP2004/007139
 Title: CHEMICAL AMPLIFICATION TYPE POSITIVE
 PHOTORESIST COMPOSITION AND RESIST PATTERN
 FORMING METHOD
 Express Mail Label No.: EV 307993573 US

Direct all correspondence to Customer No.: 20995Date: January 19, 2005
Page 1 of 2

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The following enclosures are transmitted herewith to be filed in the patent application of:

Inventors:

- | | |
|----------------------|------------------------|
| 1. Kenji MARUYAMA | 2. Masaki KURIHARA |
| 3. Ken MIYAGI | 4. Satoshi NIIKURA |
| 5. Satoshi SHIMATANI | 6. Masahiro MASUJIMA |
| 7. Kazuyuki NITTA | 8. Toshihiro YAMAGUCHI |
| 9. Kousuke DOI | |

APPLICATION ELEMENTS:

- (X) This is a FIRST submission of items concerning a filing under 35 U.S.C. § 371.
- (X) The U.S. has been elected (Article 31).
- (X) A copy of the International Application as filed (35 U.S.C. § 371(c)(2)) has been communicated by the International Bureau.
- (X) An English translation of the International Application as filed is attached hereto.
- (X) Amendments to the claims of the International Application under PCT Article 19 (35 U.S.C. § 371(c)(3)) have not been and will not be made.
- (X) A Declaration and Power of Attorney in 4 pages.
- (X) Recordation Form Cover Sheet and Assignment in 4 pages.

OTHER APPLICATION PARTS:

- (X) Preliminary Amendment: Amendments to the specification are attached hereto on page 3.
- (X) Information Disclosure Statement and PTO-1449 in 3 total pages (IDS and 1449).
- (X) 21 references
- (X) International Search Report (PCT/ISA/210).
- (X) PCT Forms: PCT/RO/101; PCT/ISA/220, 237; PCT/IB/301, 304.

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DT1 Rec'd PCT/PTO 19 JAN 2005

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Page 2 of 2

- (X) A copy of International Application as published (WO 2004/104702 A1).
(X) Return prepaid postcard.

FILING FEES:

(949) 760-0404 FEE CALCULATION				
FEE TYPE		LARGE FEE	CALCULATION	TOTAL
Basic Filing Fee		1631 (\$300)		\$300
Search Fee		1632 (\$500)		\$500
Examination Fee		1633 (\$200)		\$200
Excess Claims	29 - 20 =	1615 (\$50)	01 9 x 50 = 450.00 DA	\$450
Excess Ind. Claims	5 - 3 =	1614 (\$200)	2 x 200 =	\$400
Multiple Claim		1616 (\$360)		\$360
Assignment		8021		\$40
			SUB TOTAL	\$2,250
			TOTAL FEE DUE	\$2,250

- (X) A check in the amount of \$2,250 to cover the Total Fee Due is enclosed.

The Commissioner is hereby authorized to charge any additional fees which may be required, now or in the future, or credit any overpayment to Account No. 11-1410.



Daniel E. Altman

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DAH:111410 Name/Number:10522036
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Registration No. 34,115
Attorney of Record: 07/11/2005 PBOOKER 0011270200
Customer No. 20,995
Name/Number:10522036
FC: 9204 \$100.00 CR

ATTACHED SHEET

PRELIMINARY AMENDMENT

Prior to the first line of the specification on page 1, please insert the following paragraph:

--This application is the U.S. National Phase under 35 U.S.C. §371 of International Application

PCT/JP2004/007139, filed on May 19, 2004, which claims priority of Japanese Patent

Application Nos. 2003-141805 and 2003-426503, filed on May 20, 2003 and December 24, 2003 respectively. The International Application was published under PCT Article 21(2) in a language other than English. --

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Daniel E. Altman

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Attorney Docket No. : SHIGA7.004APC

Applicant(s) : MARUYAMA, et al.

For : CHEMICAL AMPLIFICATION TYPE
POSITIVE PHOTORESIST COMPOSITION
AND RESIST PATTERN FORMING
METHOD

Attorney/Agent : Daniel E. Altman/Katsuhiko Arai

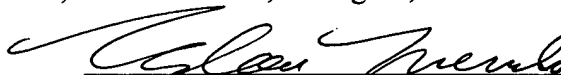
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I hereby certify that the accompanying

Transmittal letter (including attached sheet for Preliminary Amendment) in 3 pages; Specification in 82 pages; ; **SIGNED** Declaration and Power of Attorney in 4 pages; Recordation Form Cover Sheet and Assignment in 4 pages; International Application as Filed (PCT/RO/101); International Search Report (PCT/ISA/210); Information Disclosure Statement, PTO Form 1449 with 21 references; International Application as Published (WO 2004/104702 A1); PCT Forms: PCT/ISA/220, 237; PCT/IB/301, 304; \$2,250 Check for Filing Fee and Assignment Recordation Fee; Return Prepaid Postcard

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